

REMARKS

In the outstanding Official Action, claims 1-9 were deemed to be allowable, while claim 10 was rejected under 35 USC 102(b) as being anticipated by Beasom, for the reasons of record. The Examiner's Statement of Reasons for Allowance of claims 1-9 indicated that thermally oxidizing the device to oxidize the polysilicon plug to form an oxide plug at the base of the trench constituted patentable subject matter.

In order to place claim 10 in condition for allowance, this claim is herewith amended to recite subject matter analogous to that of allowable claims 1-9, in that it is now recited that a thick oxide plug is formed only of thermally oxidized doped polysilicon at the base of the trench extending into the drain region. This limitation, as now more positively and precisely recited, is directly contrary to the cited teaching of Beasom in this regard (at col. 5, lines 1-20), wherein it is expressly disclosed that the material at the base of the trench is "a composite of thermally grown and deposited silicon oxide". Such a structure is clearly patentably distinguishable over the structure as now more specifically recited in claim 10 wherein the material at the base of the trench is formed only of thermally oxidized doped polysilicon.

In view of the foregoing, it is respectfully submitted that claim 10 now substantially includes the relevant patentable subject matter of claims 1-9, and that this subject matter is neither shown nor suggested in Beasom. Accordingly, allowance of claim 10 is respectfully submitted to be justified at the present time, and favorable consideration is earnestly solicited.

Respectfully submitted,

By 
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